



2818

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

TUE NGUYEN

Application No.: 09/898,439

Filed: July 5, 2001

For: Plasma semiconductor processing system
and method

Examiner: Hoang, Quoc Dinh

Art Unit: 2818

AMENDMENT

#6/a
w/ Drawg.
marsha
2/4/03

Assistant Commissioner for Patents

Washington, D.C. 20231

Sir:

In response to the Office Action dated October 25, 2002, please amend the
above-referenced application as follows.

IN THE DRAWING:

In Fig. 1A, please add reference 100 to show the plasma processing system,
reference 106 to show the plasma excitation circuit, reference 110 to show the plasma
generator. A new drawing of Fig. 1A is included.

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